

**EROSION MITIGATION FOR COLLECTOR OPTICS
USING ELECTRIC AND MAGNETIC FIELDS**

ABSTRACT OF THE DISCLOSURE

[0044] A magnetic and/or electric field may be generated around collector optics in an EUV lithography system to deflect debris particles from the reflective surfaces of the optics. The magnetic and/or electric field may be generated by a solenoid structure around the optics or by passing current through inner and outer shells in a nested shell arrangement.

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